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IN THE CLAIMS

1. (Original) A CMP abrasive comprising:
a ceria slurry; and
a chemical additive having two or more functional groups by mixing and synthesizing a polymeric molecule and a monomer.
2. (Original) A CMP abrasive as defined in claim 1, wherein said ceria slurry comprises ceria powder, water and negative-ion-based polymeric compound and conforms to a Newtonian viscosity behavior.
3. (Original) A CMP abrasive as defined in claim 2, wherein said negative-ion-based polymeric compound is selected from the group consisting of polymethacrylic acid, ammonium polymethacrylate, polycarboxylate and carboxyle-acryl polymer.
4. (Currently Amended) A CMP abrasive as defined in claim 1 ~~or 2~~, wherein in said chemical additive, said polymeric molecule is polyacrylic acid (PAA), and said monomer is selected from the group consisting of acrylamide, methacrylamide and ethyl-methacrylamide.
5. (Original) A CMP abrasive as defined in claim 4, wherein mixing ratio of said slurry to said chemical additive is 1:1.
6. (Currently Amended) A CMP abrasive as defined in claim 1 ~~or 2~~, wherein in said chemical additive, said polymeric molecule is polyacrylic acid (PAA), and said monomer is vinylpyridine or vinylpyrrolidone.
7. (Original) A CMP abrasive as defined in claim 6, wherein mixing ratio of said slurry to said chemical additive is 1:1.

8. (Currently Amended) A CMP abrasive as defined in claim 1-~~or~~2, wherein in said chemical additive, said polymeric molecule is alkyl methacrylate, and said monomer is selected from the group consisting of acrylamide, methacrylamide and ethyl-methacrylamide.

9. (Original) A CMP abrasive as defined in claim 8, wherein mixing ratio of said slurry to said chemical additive is 1:1.

10. (Currently Amended) A CMP abrasive as defined in claim 1-~~or~~2, wherein in said chemical additive, said polymeric molecule is alkyl methacrylate, and said monomer is vinylpyridine or vinylpyrrolidone.

11. (Original) A CMP abrasive as defined in claim 10, wherein mixing ratio of said slurry to said chemical additive is 1:1.

12. (Original) A method for manufacturing CMP abrasive comprising steps of:
providing a ceria slurry;

manufacturing a chemical additive having two or more functional groups by mixing and synthesizing a polymeric molecule and a monomer in a reactor; and
mixing said slurry and said chemical additive.

13. (Original) A method for manufacturing CMP abrasive as defined in claim 12, wherein said step of providing a ceria slurry comprising steps of:

manufacturing ceria by solid-phase synthesis;
mixing said ceria with water;
milling said mixture with a high energy attrition mill;
dispersing said milled resultant with a high pressure dispersion apparatus; and
dispersion stabilizing said dispersed resultant by adding negative-ion-based polymeric compound.

14. (Original) A method for manufacturing CMP abrasive as defined in claim 13, wherein said negative-ion-based polymeric compound is selected from the group consisting of polymethacrylic acid, ammonium polymethacrylate, polycarboxylate, and carboxyle-acryl polymer.

15. (Currently Amended) A method for manufacturing CMP abrasive as defined in claim 13-~~or 14~~, wherein said negative-ion-based polymeric compound of 0.0001 ~ 10% by weight is added.

16. (Original) A method for manufacturing CMP abrasive as defined in claim 13, after said step of dispersion stabilizing, further comprising a step of removing large particles with a filter.

17. (Currently Amended) A method for manufacturing CMP abrasive as defined in claim 12-~~or 13~~, wherein the molecular weight of the polymeric molecule is 2,000 ~ 1,000,000.

18. (Currently Amended) A method for manufacturing CMP abrasive as defined in claim 12-~~or 13~~, wherein said step of manufacturing the chemical additive further comprises a step of adding further solvent to the synthesized chemical additive.

19. (Original) A method for manufacturing CMP abrasive as defined in claim 18, wherein said step of adding further solvent causes the synthesized chemical additive to be 0.03 ~ 10% by weight.

20. (Currently Amended) A method for manufacturing CMP abrasive as defined in claim 12-~~or 13~~, wherein in said chemical additive, said polymeric molecule is polyacrylic acid (PAA) or alkyl methacrylate, and said monomer is selected from the group consisting of acrylamide, methacrylamide, ethyl-methacrylamide, vinylpyridine, and vinylpyrrolidone.

21. (Original) A method for manufacturing CMP abrasive as defined in claim 20, wherein the mixing ratio of said slurry to said chemical additive is 1:1.